

Supplemental document

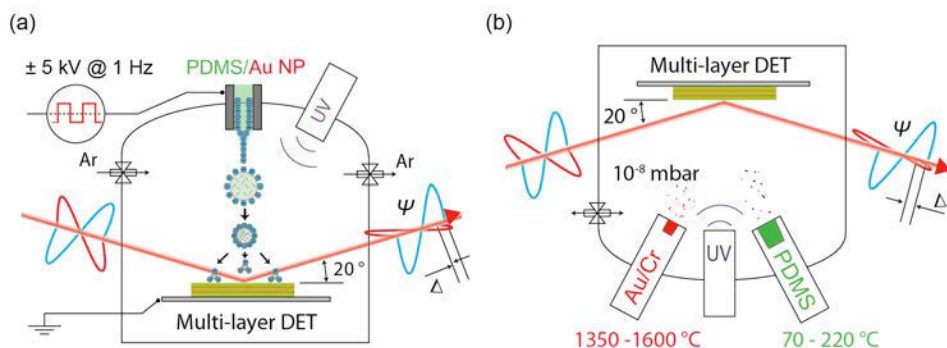


Figure 1. Schematics of experimental setup for the fabrication of DETs using (a) electro spray deposition (ESD) and (b) organic molecular beam deposition (MBD) system. Spectroscopic ellipsometry serves for the *on line* monitoring of the film growth.

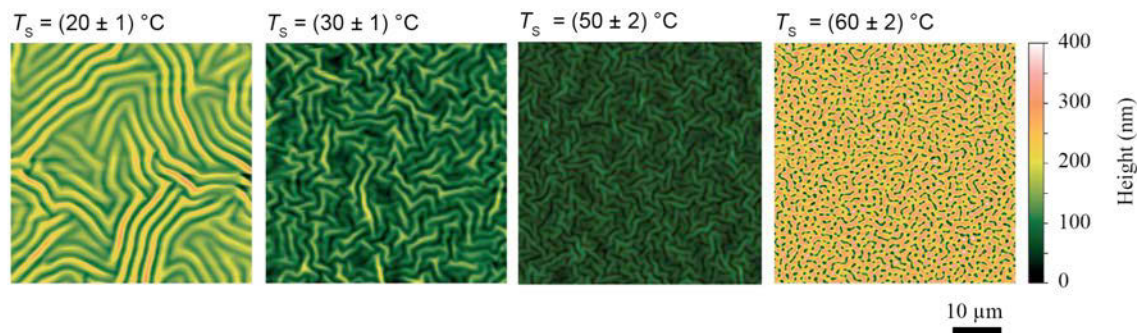


Figure 2. The morphology of (350 ± 50) nm-thick silicone films, oxygen plasma treated at selected substrate temperatures T_s . The substrate temperature determines the formation of nanostructures: wrinkles at $T_s = 20$ °C and sub-micrometer knobs at $T_s = 60$ °C.

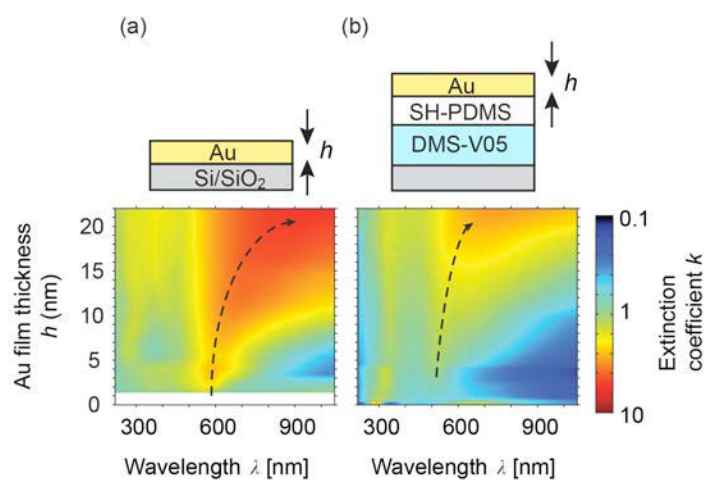


Figure 3. Plasmonics of growing Au. The film-thickness-dependent spectroscopy results of the extinction coefficient k are shown for thermally evaporated Au (a) on SiO_2/Si and (b) on thiol-functionalized silicone thermally deposited on a UV-cured commercially available elastomer film.